

Masarykova univerzita
JUDr. Pavel Vacek
Žerotínovo náměstí 617/9
601 77 Brno
IČ: 00216224

V Zastávce dne 19. 12. 2014

Věc: Žádost o dodatečné informace k zadávacím podmínkám veřejné zakázky „Rastrovací Augerova mikroskopie – CEITEC MU“

Žádáme Vás tímto o dodatečné informace k veřejné zakázce s názvem „Rastrovací Augerova mikroskopie – CEITEC MU“.

Dotazy:

1)

In the line Fast entry chambre you wrote: „Fast entry chamber is used to introduce and to transport samples into the analytical chamber without breaking vacuum. Fast entry chamber and analytical chamber are separated by a valve and interlock.“

Question: Do we understand the specification right if we assume it would be fulfilled by a system that has a manual gate valve between the fast entry chamber and the analytical chamber as a separation and an interlock for vacuum protection between the analytical chamber and the pumping system?

2)

In the line Sample holder you wrote: „The sample holder has at least four electrical contacts, the sample can also be connected to two impedance matching wires with connectors for the transmission of high frequencies up to 6 GHz at least.“

Question: Do we understand the specification right if we assume it would be fulfilled by connectors which are rated for 6 GHz? We will confirm the specifications by providing the specifications sheet of the third party provider.

3)

In the line Beam current you wrote: „The beam current in a minimum of 50 nA at an energy of 15 keV and a resolution of 12 nm and 28 nA at 3 keV energy with resolution 18 nm. Resolution measured by 20% - 80%.“

Question: Do we understand the specification right if this is a general third party vendor specification and we prove this resolution by dark space resolution on a Au-C sample during the acceptance test?

4)

In the line Detection you wrote: „The total pulse counting detection with > 70 Mcps (Mega counts per second) integral count rate for a minimum of 7 channels and variable slit mechanism for optimisation of the resolution.“

Question: Do we understand the specification right if the >70 Mcps integral count rate is a general specification of the analyzer? During the acceptance test we would show the following:

Intensity > 12000 cps per nA and channel for the 352 eV Ag peak at CRR 4 (0.5% resolution), i.e.

> 420 000 cps for typical configuration (5 nA, 7 channels)

Intensity at 5 keV primary beam energy, with sample tilt 30°* with respect to primary beam, ion-sputtered Ag sample bulk material. Working distance: 8 mm. Beam current measured using a Faraday-cup.

Signal is: peak intensity minus background.

5)

In section SEM, SAM in the line Image drift you wrote: „Image drift is <10 nm/10 hours. The system allows controled compensation of the drift.“

And in the section SEMPA, line Image drift you wrote: „Size of image drift <10 nm/10 hours. The system allows control drift compensation. „

Question: Do we understand the specification right if we assume it would be fulfilled by having image features staying in a radius of 10 nm in 10 hrs as shown on the screen image during the acceptance?

Vzhledem k závažnosti dotazů Vás žádáme o prodloužení lhůty pro podání nabídky o 14 dnů.

Předem děkujeme za vyřízení naší žádosti.



Měřicí technika Morava s.r.o.
Tř. 1. máje 102, 664 84 Zastávka, ČR
IČ: 29316715, DIČ: CZ29316715

Dr. Dušan Novotný, jednatel

Měřicí technika Morava, s.r.o.